

32. The photoresist of claim 29 wherein the polymer comprises alkyl ester groups.

33. The photoresist of claim 29 wherein the polymer comprises polymerized alkyl acrylate groups.

34. The photoresist of claim 33 wherein the alkyl acrylate groups comprise an optionally substituted cycloalkyl group having 3 or 4 ring carbon atoms.

35. The photoresist of claim 29 wherein the optionally substituted cycloalkyl group having 3 or 4 ring carbon atoms is a component of a polymerized acrylate.

36. The photoresist of claim 29 wherein the photoresist consists essentially of the photoacid generator compound and the polymer.

37. The photoresist of claim 29 wherein the photoresist consists essentially of the photoacid generator compound, the polymer and a base component.

38. An article of manufacture comprising a substrate having coated thereon a photoresist composition of claim 29.

39. The article of claim 38 wherein the substrate is a microelectronic wafer.

REMARKS

Claims 19-28 have been cancelled without prejudice, and claims 29-39 have been added. No new matter has been added by virtue of the new claims. For instance, support for the new claims appears at pages 10-12 and the original claims of the application.